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MICROELECTRONICS TECHNOLOGY: PROBLEMS AND PERSPECTIVES IN COUNTRIES OF WEST ASIA AND NORTH AFRICA.

The paper is a result of a UNIDO sponsored mission in Iraq, Saudi Arabia UAE (Abu Dabi), Tunisia and Morocco. The author wishes to record his appreciation to the sponsors for making his trip possible, UNECWA officials for their assistance and encouragement and UNDP officers i visited countries for their help in administrative matters and for organising certain visits. Finally, the author would like to thank the members of the mission Mr Felix Hinc and Mr Hassan Charif for their excellent cooperation and many valuable discussions. The contribution of the latter deserves special mention due to his profound knowledge of the region and extensive contacts with key people in the field which were invaluable in achieving mission objectives.

The mission was conducted in November-December 1983 and this paper is based on meetings with over a 100 people in 45 organisations spread over 25 days. The organisations covered include government ministries, national computers centres, major oil and mineral companies, investment and planning institutions, academic, R & D and manufacturing organisations. Since such an exercise was being attempted for the first time coverage has been extensive in order to obtain a perspective of the status, problems and potential for microelectronics in the region. However, these notes represent impressions of a 3 week visit only, at a given period in time, with the primary objective of preparing a backgroung paper for the experts meeting in Kuwait in March 1984.

The countries in the UNECWA region and North Africa recognize both the need and potential for the application and development of microelectronics technology explicity is well ahead of the absorptive capacity of the region both in terms of infrastructure and human resources. Finance clearly is not a constraint, especially, in the oil exporting countries of the region. Consequently, the present situation does not tend toward a stable technological equilibrium and special efforts will be necessary both in terms of infrastructure development and local manufacture if the present rate of diffusion of the technology, assuming effective utilisation, is to be maintened.

We ile special efforts to develop applications of this technology have been made in the public domain, as is evident from the chain of national computers centres that have been established, there is a considerable spread in the capabilities of individual countries. Thus, CNI in Tunis and IMEG in Casablanca/Rabat seemed to be considerably ahead of their counterparts in the other countries both in terms of human resources and methodology. Greater regional cooperation with the assistance of UNECWA/UNICO between these institutions could go a long way in not only rectifying the imbalance but further upgrading capabilities.

In terms of industrial applications, the largest market for microprocessors based control systems was the oil production/exploration and mineral extraction/purification sectors. Thus, while ARANCO, Saudi Arabia the largest oil exploration/production company was an impenetrable fortress tied to primarily US vendors for the both hardware/software support, the situation in ADNOC, Abu Dabi, and PETROMIN, Saudi Arabia appeared relatively more flexible with greater potential for development of local capabilities to support their future

requirements for microelectronics hardware and software. Similarly, OCP, Casablanca, Morocco and probably the Jordanian Phosphate Company are fare more open and keen to use / develop local capabilities. Another application area of considerable potential for the region was in the generation, transmission and distribution of electricity and the example of STEG, Tunis deserves to be supported and emulated. Finally, the largest potential for the application of microelectronics technology is in the education and office automation sectors as brought out succinctly in the paper of W.M. Turski provided the problem of standardisation of the Arabian character set can be swiftly and unambigously resolved.

Herein also, lies an opportunity of volume manufacture of low cost bilingual terminals and microcomputers. The efforts of Saudi Arabia (Al-Farabi computers), IMEG (low cost micros for schools) and CNI (terminals) need to coalesced and catalysed effectively by UNIDO/ECWA.

The manufacturing base in both the ECWA and North Africa region is presently very limited and would have to be considerably augmented to sustain an autonomous microelectronics industry. Given the gross national product of the region and its continuously increasing requirements for microelectronics products, there is a definite need to evolve a strategy for the development/manufacture of microelectronics products/components for the region. The present efforts at TV assembly at SADA, Morocco, SONELEC, Algeria or in Tunis and Syria nor the offshore assembly of components at SNRF, Morocco of their manufacture to a limited extent at SONELEC, Algeria constitute a viable or effective strategy for the future development. In the experience of the mission, Tunis was the only country where the potential to set up local manufacture on an integrated basis was being seriously examined, primarly, by BDET and API. Thus, 3DET was talking to both Jeumont Schneider. France to establish manufacture of EPARXS (10,000 lines per year) and to COMTERM, Canada, to manufacture terminals, while API

wanted to establish of passive components i.e. resistors and capacitors. Both institutions, however, were clearly aware and concerned about the economic viability of these projects and were looking for a wider regional market.

In the author's view, exclusively national strategies cannot be pursued by individual countries in the region since the requisite combination of high per capita income and population does not simultaneanusly co-exist. On the other hand, the electronics market for the region as a whole is substantial enough to pursue an economically viable developed and growing at a significant rate. Two sectors which need to be singled out are consumer electronics and communications. While it was not possible to obtain any quantitative data on the consumer sector, the fact that production of color TV sets exceeds 100 per day in both Morocco and Algeria, each with a population of 30 millions approximately and 50,000 in Tunisia with a population of 6-7 millions, the color TV market in the ECWA + North Africa region as a whole ought to exceed 1,5 millions sets per annum. If to this is coupled the demand for VCRs, combination sets, calculators, personnal computers and electronic watches, this market is estimated to be in the neighbourhood of \$\beta\$ 2 billions.

An earlier ECWA/UNIDO study shows that the demand for telephone exchange lines is the ECWA regions is projected at 433,000 per annum during the period 1981-85 growing to 796,000 per annum between 1986-1990 with a matching demand for ECH channels. The corresponding demand for telephone sets has been estimated at 563,000 and 1,035,000, respectively. Further, the average annual investment in the regions networks has been estimated at \$886 millions (1981-85) and \$1,622 millions (1986-1990).

The estimate is based on a educated conjoncture given the GNP, population, present level of assembly and visibility of these products.

While no accurate estimates exist for the computer market in the region, Saudi Arabia alone has been importing equipment at the rate of \$ 100 million/year during 1981 and 1982. Similarly, the requirements for microelectronics, especially, microprocessor based process controls for the oil exploration/production is significant as discussed in the report of the mission. Further, standardisation of the Arabian character set could considerably stimulate the demand for micros and terminals in schools and the office, respectively.

Given the above demand, production of a range of active and passive electronic components clearly appears to be a viable proposition. In the consumer sector for the type of products indicated above, components represent almost 40-50% of the value of these products. Similarly, in the area of switching, the cost of components per line for a system like the E 10 B of CIT-ALCATEL is \$ 125/line, namely 50% of the cost per line. While clearly a more detailed study is required to accurately assess present requirements and future demand in these sectors, once this has been done, it would not be too difficult to extract a profile of component requirements both in terms of quantity and value. A pricri, it would appear that adequate demand exists for establishing a viable component industry. However, it must be recognized from the outset that such an industry would only be viable if it was established on a regional basis. Consequently, standardisation of hardware must constitute an important element of such a strategy. Clearly, the regional issues involved in an industrial strategy for microelectronics need a closer examination, which is not the purpose of this paper.

Several suggestions have been made in Turski's paper for augmenting the software capabilities in the region. A complementary set of measures to upgrade the regions "hardware" capabilities is essential if a composite and autonomous microelectronics capability is to be established. These are discussed below:

There are 2 major microprocessor families with extensive applications and software currently in vogue, namely, the 8 and 16 bit families of Intel and Motorola. The orientation of the former is primarily towards the personal computer market, and even more so after IRM's entry. Motorola's 6800 and 68 000 series on the other hand are more extensively used for industrial process control applications. The applications coverage and some of the hardware features of these series is summarized in Tables 1 and 2. There are several processor, memory, interface and controller modules together with debugging software packages and development support tools available. Several major semiconductor/system companies have thrown their support behind these series, namely, HITACHI, MOSTEK and THOMSON, thus providing the requisite back up to ensure its continued use. There is a need to establish a regional capability in systems integration around such a concept. In order to ensure effective implementation of such a concept a core group of the more willing users, partly identified above, together with a group of experts from the academic sector needs to be formed with necessary support from ECWA/UNIDO to prepare a feasibility report in terms of the regions requirements in the major application areas, i.e. on exploration/production, mineral extraction/purification and power generation/distribution, etc. Based on these findings a regional centre could be created with appropriate linkages for technology transfer both with OEM suppliers of such components and system suppliers.

The key element in any future strategy to design and build electronic systems is the ability to design the silicon "chip". All IC's technology is built on the foundation of semiconductor device physics which provides the essential knowledge is semiconductor fabrication technology which allows the designed IC's to be physically constructed and above this in turn is the body of circuit and logic design knowledge. Various areas of knowledge in the manufacture of IC's have reached different stages of development, with the higher level design skills being the least highly developed. In fact, all the evidence available strongly suggests that these traditional skills will not enough for VISI, design methodology is in essence a search for the right approach to built computer-aided engineering systems that will go on to design the IC's semi-automatically. There is a shift from hardware concepts. It appears reasonably certain that the whole area of the design of highly concurrent systems will become one of the most rapidly developing technological fields of the coming year. All these changes are likely to affect the future structure of the industry in terms of being integrated both in terms of design and fabrication as at present.

It is likely that design will become increasingly decentralised and the concept of the "silicon foundry" which does primarily fabrication develop. The emergency of the large custom and semi-custom markets in the eighties is a consequence of this change. Further, design automation systems in terms of both hardware and software in unbundled form are becoming increasingly available. The "work station" which is a low cost design system is becoming increasing viable and several of these systems are being marketed. While the concept of decentralised desgin works quite well in a "foundry" rich environment as has been demonstrated by the sucess of the "multi-project chip", in a developing

country environment it is important that local design capabilities are supported by at least a pilot level "silicon foundry" with the capability to process wafers using at least one stable technology. Obviously, local design centres could still need to have linkages with other silicon foundries in both Europe and the USA. Since the concept of the "silicon foundry" is most prevalent in the USA a list of such foundries is summarized in Table III.

A ISI design centre necessarily has 2 components, namely, hardware and software. In terms of hardware the most extensively used system by far is the VAX II/780. The system has the great advantage that most of the software packages available for ISI design can be directly implemented on it without any modifications. While it is not proposed to go into the details of the hardware configuration, the VAX II/780 uses graphic terminals which constitute the man machine interface. Depending on the configuration the hardware costs for establishing a design centre would be typically S 300,000. The design software could have to include a package for registrer level entry, a logic simulator (TEGAS, SPLICE, EPILOG), a circuit simulator, (SPICE), preferrably a processor simulator (SUPREME), an interactive graphics backage (CAIMA, GCI, etc...) a package for design rule check, a cell or element extractor from the lay out to verify or resimulate the logic, software for a PG tape output for mask fabrication and cell library with a data basis containing the requisite design rules i.e. layout and electrical. There are several vendors for such packages besides some of them are also available from universities in the USA. However, while integration of unbundled software from multiple sources is more economic it is also that much more difficult to implement. The output of a design centre

is a PG centre from which the mask set for processing the "chip" is fabricated, either using a laser pattern generator or a E-Beam machine. While several mask fabrication shops are available in the USA and Europe, if it is decided to set up a pilot "silicon foundry" for wafer fabrication, then it could also be necessary to set a mask fabrication facility.

As a first step it would be important to establish a regional design centre on a immediate basis for which requisite support should be provided by UNIDO. Such a centre should play a modal role in creating a chain of national design centres in a optimally cost-effective manner i.e. by shar. the software resources. In order to ensure synergy all national centres and the regional centre should be networked together or at least linked by electronic mail. It would then be possible to rapidly create a corps of designers in the region and thus lead to rapid diffusion of the technology. An important goal of such a programme should be software development, to upgrade the design tools and build the next generation of design automation systems.

The second level of interconnection in a electronics systems is conventionnally provided using printed circuits boards (PCB), and they tend to have 2 or more levels for professional systems. The capability to design and fabricate double sided PCBs with through hole plating was only available at SNRF, Morocco a Thomson subsidiary. Similarly, the mission did not see any evidence of the design and fabrication of hybrid circuits through here again the assembly of thick film hybrids was being done at SNRF based on imported screened substrates and other active/passive components. While the ability to design and fabricate both the above components is a essential prerequisite to built microelectronics sub-systems/systems, equally important is the ability to populate and test these sub-assemblies. A regional centre needs to be

established to fill this gap with additional important function of training personnel in these techniques from the countries of the region. Support for such a concept from existing/potential manufacturers of sub/systems needs to be sought in order to promote the above concept . Further, ECWA/UNIDO could provide the necessary technical inputs needed in planning such a facility.

The region has several excellent schools of which the Technological University, Baghdad, UPM, Saudi Arabia and ENSET and ENIT, Tunisia deserve special mention. In terms of computing capabilities UPM is clearly ahead of all other institutions visited with a VAX II/780, further gives it a head sart to establish a centre for ISI design. However, as been pointed out while considerable emphasis was being placed on the applications and software aspects of microelectronics, there was an a finite need to augment the hardware aspects of the technology i.e. materials science, semiconductor device fabrication techniques, CAD for chip design etc... In this context the approach of The Centre for Integrated Systems (CIS), Stanford University is worth emulating. CIS seeks to integrate solid state research and fabrication on the one side with applications on the other. The intention is to merge the three disciplines of the electronics age computer science, information cience and physical science. In order to make the system synergistic it is proposed that the scientists working in solid state physics will investigate the fundamental principles of IC's and pass their results to the IC's engineers. These engineers will use that knowledge to design new devices and fabrication techniques, and give them to the application engineers, who turn will define new systems and integrate the chips into complete functional systems. Concurrently, the computer and information scientists are developing the tools to design ant test the IC's and so on. The concept brings together all the composite skills and tools to solve the increasingly complex problems of tomorrow.

The communications infrastructure in the ECWA region is being developed at a rapid rate. There is a general trend to shift to electronic switching systems, as witnessed in Morocco and Tunisia. Similarly, Jordan and Egypt have opted for CIT ALCATEL'S E 10 B system which is digital with Saudi Arabia having gone in for ERICSON. The impression gained by the mission was that Saudi Arabia. UAE. Tunisia and Morocco had relatively efficient telephone networks well integrated internationally. The launching of ARABSAT in october 1984 will further augment the region's capability for intra-regional communications. Consequently, the time is ripe to start planning for a multi-service national/regional network which can transmet voice, data and video signals, with the long term goal of establishing an integrated services digital network (ISDN). In particular the development of local area networks, packet switching, electronic mail and teletext/viewdata is of special significance. The need to establish common standards for the systems hardware/software is of crucial importance for the future development of microelectronics in the region and UNIDO with assistance from ITU could assist in commisioning a feasibility study in this area for the region.

The application of microelectronics in the service sectors like education health and transportation is likely to produce the greatest social benefit. The awareness of this potential was highest in Morocco

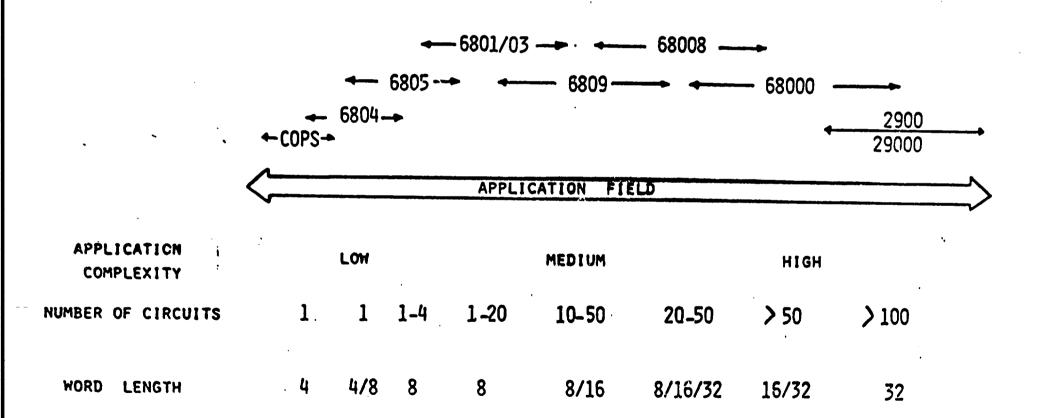
namely, at the Centre for Arabisation, Rabat and ANIT and ENSET in Tunis. There is a need to focus these efforts into a wider regional one and the methodology suggest in Oliphant's paper, "Microprocessor Applications in Developing Countries" (UNIDO, 1982), to establish a hierarchy of microprocessor applications development centres with the requisite hardware/software tools and suitable institutional support could form an useful basis for preparing an implementation plan for the region.

The problems of equipment maintenance and the lack of availability of components spares was pointed out by several organisations. Equipment maintenance can be segregated into two categories, computers and other equipment. A specialised corporation to deal with computer maintenance has been quite successful in the indian context and a modified version of such a concept to meet regional requirements merits a cluser examination. Other electronic equipment covers a wide range and spectrum and includes analytical, measuring and medical instrumentation and its meintenance in view of the large variety of types and vendors is more difficult and no simple solution exists. The programme at ENIT, Tunis to train high level technicians for maintenance needs to be more closely analysed to determine the extent of its sucess and the need for further support and diffusion of the approach. Finally, all development programmes in the region seemed to suffer due to lack of component availability one possible solution to this problem could be to set up a regional component bank which stockpiles a list of priority components with support from ECWA/UNIDO.

MICROPROCESSOR

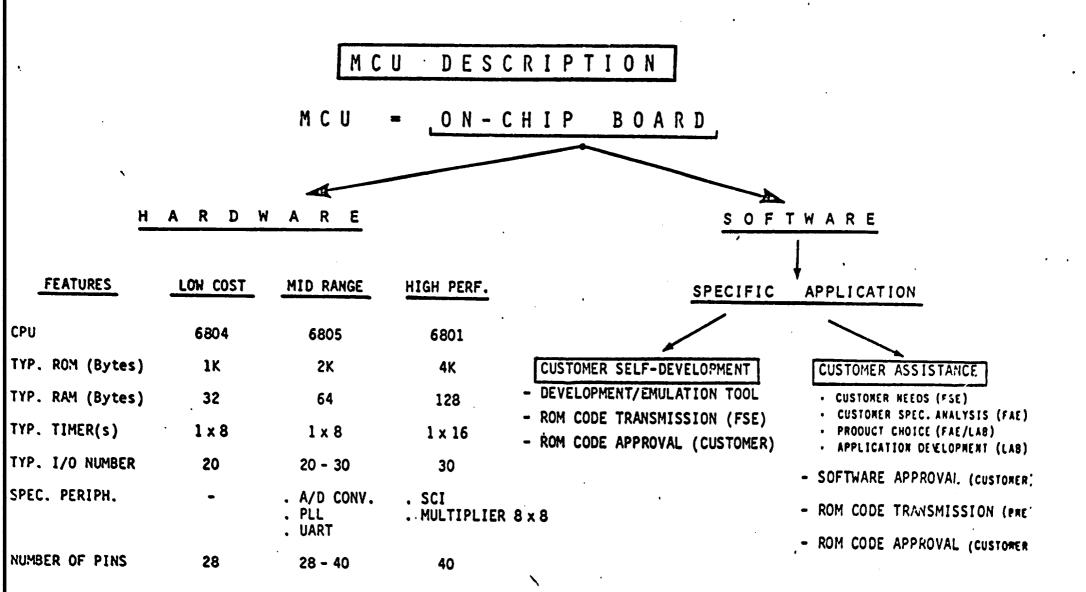
AND PERIPHERAL

### MICRO APPLICATION COVERAGE



⊃ S REFERENCE MANUAL

TABLE 2



				num Featur	res Averlab re Size Gate n attown in p				Maximum Production	Cost Pur		
Company Contact Person	Me-G	WOS S-G	Me-G PA	MOS S-G	M-G C	MOS Si-G	Bipoler	Prod. Wuler Size	Requirements (S or waters per year)	Prototype Run (with prod cost, If everlable)	Design Formet from Customer	
Acrian, Inc. 10000 Bubb Road Cuperano, CA 95014 (408) 996-8522 Jim Huskens VP of Mg.	у Бұлп (10 <sub>9</sub> лп)				ј Бµт (10µт)		•	2	\$10,000·ye	nMOS: \$3,000 per 25 waters CMOS: \$4,000 per 25 waters Bipolar: \$25 per water, per mask layer	Masks, Celma tape, PG tape	
American Microsystems, Inc. 3800 Homestead Roed Santa Clars. CA 95051 (408) 246-0330 Jeny Crosby Product Manager, COT Products		J.Sym (nMOS I) Sym (nMOS II) Sym, Gym	7.5µm		<i>ј</i> 7.5µm	/ 5µm (CMOS I), 3µm (CMOS II) single or double metal		ų	Working plate plate input: \$75,000 yr. PG or Calma ir.put: 10 times angi- teering cost for first year	Development cost: \$14,000 to \$30,000	Caima tape, PG tape, working plates	
ASEA HAFO 66 Bovet Road Sari Mateo, CA 94402 (415) 574-5400 Anders Dejenfelt, Sales Manager		•	•		J Syste (Byste)	/ 2µm (10;:m) CMOS: SOS	·	*	One batch (40 me-pate CMOS waters or 20 CMOS/ SOS waters)	\$20,000 (incl. mask and water- tab charges)	Masks, PG tape, CIF (PG tape or CIF preferred)	
Cherry Semiconductor Corp. 2000 S. County Trail E. Greenwich, RI 02818 (401) 885-3600 David Pryce Marketing Manager		-					finear, ffL, eptoelect.	r	1/10 waters/ snorth	\$3000 per engineering run (10 waters) Prod cost: \$120 to \$160 per water (1,000 to 5,000 waters/mo.)	Applican tape, Calma tape, masks, scaled drawings	
Citel 3050 Raymond Street Senta Clara. CA 95050 (408) 727-6562 Gary Hess Marketing Director	ار 5µm (10µm)	/ 3µm (8µm) 4µm (8µm) 5µm (10µm)	/ 5µm (10µm)	ر 5 <sub>p.</sub> m (10 <sub>p.</sub> m)	/ 5µm (10µm)	-/ 3µm (Ցµm) 4µm (Ցµm) 5µm (10µm) 5µm 2-łayer poly	Linear 6μm, f <sup>2</sup> L Sμm	3° and 4°	Lot: 25 water starts	Variable	Calma tape, masks, PG tape	
Comdial Semiconductor Serv. 1230 Bordeaux Drive Sunnyvale, CA 94086 (408) 744-1800 Gery Kennedy VP and General Manager		/ Յրտ (Ցրտ), 4րտ (Ձրտ)				/ dum (Bum), dum (Bum), 2-layer poly, Sum (Bum)		t.	25 walers (Comdul apocalizes in quick- tumeround prototyping)	\$7000 to \$8000 for Jum HMOS (10 or 15 duys) \$7000 to \$7000 for 4µm CMOS (10 or 15 days) Consult factory for other requirements	Calma tape, CIF, masks, e-beam tape	
Exar Integrated Systems, Inc. 750 Patoniar Avenue Europycale, CA 94088 (460) 732-7970 Tiruston Awall		J Syam			Sport.	Sp.m	j Linear, . PL	*	250 waterstyr.	Consult factory	Celma tapo, masks (pveterned)	

Post White- Processing Services (water probing packaging, testing, etc.)	Normal Tumeround Time	Water Acceptable Critens (std. proces* control mo stor)	Technical Interaction Between Foundry and Customer	Availability of Design Rules for Venous Processes	Must Customer Sign Non- disclosure Agreements	Simulator Parameters Available	Second- Source Agreements	WR Foundry Modify Process?	Processes Available Within Next & Months
(none)	Masks to waters: 6 wis. PG tape to waters; 10 wis.	Test monitors supplied by Acrush or by customer	Intel engi- neering raview; updates as required	A	Ves	Pricess emu- lation support via PRODEM (similar to SUPREM)	(none)	Ves	Rad hard me- gate CMOS June 1963 Sigate CMOS (Spm): Nov. 1963
Probing. packaging. packaged- part testing	PG tape to cut-and- go's 4 to 5 wis Database tape to cut-and-go's: 5 to 6 wis. PG tape to packaged parts: 7 to 10 wis.	AMI process control montor on all waters; will add customer PCM ill requested	Formal review etter each phase of AMI development cycle (optional)	Avartable for all processes	Yes	ASPEC	In negobation with several companies	Yes (V; and implants)	nMOS III (2µm): 3083 CMOS I (shrink to 4µm) 3023 CMOS II (10V): 2083 CMOS III (2µm): 1084 EEPPROM process: 4084
Probing, packaging, packaged- part testing, burn-in	PG tape to wafers: 6 wis (CMOS) 7 wis. (CMOS:SOS) Add 3 wis for packaging testing	ASEA HAFO- supplied process- param modules (PPMs) and yiuld- measurement modules (VMM's)	Initial review	All processes provided	Ves .	SPICE 2G4 and SPICE 2G5	Process is RCA- companble	Yes, (large order)	4-inch process time with dry processing and positive photo- resist 4Q83
Probing, packaging, testing	8 wks. (typical) Design rule cher'., 1 wk.; Mask generation, 2 wks.; Fabrication, 5 wks.	Chemy- supplied PCM	Design reviews to establish crount process requirements	AJ	Maybe	ISPICE (NCSS)	Yes (not specified)	Yes	(none contemplated)
Probing, packaging, packaged- part testing	Masks to packaged parts (production parts, hybrai) nMOS pMOS 6-8 wks CMOS, 7-9 wks.	Citet- or customer- supplied test circuit	Intal review	A.I	Ves	Electrical (not simulator) parameters supplied	(not specified)	Depends on individual case	4" bipolar capability. Dec 31, 1983
Probing, packaging, packaged- part tosting	Masks to waters (prototype): 5 wkg days (HMOS) 10 wkg days (CMOS) Masks to tested waters (Ory: 500): 15 wkg days	Comdust- o- customer- supplied test device	Frital review	AS	No 、	SPICE	Unofficially, process is compatible with several large semi-conductor suppliers	Open for discussion	3-µm p-we? CMOS (6-m metal proh): 4053 3-µm n-we!! CMOS process: 4083
Probing, packaging, packagod- part testing	Masks to waters out: 4 to 6 wis. Add 2 to 4 wis. for tested devices	Example or customer- supplied PCM (in-house PCM preferred)	Initial review plus any required process metrices	AI	Yes	(not svalable)	Rohm (parent company in Japan)	Yes (negotable)	(not specified)

				num Feetu	res Aveleb e S-ze Get h shown in		)		Mountum Production	Cost Per	Design Format trom Customer	
Company Contact Person	M-G	MOS 8-G	Me-G	vos s-G	Me-G	MOS 8-G	Bipoler	Prod Weler Size	Procurements (5 or weters per year)	Prototype Run (with prod cost if available)		
Four-Phase Systems, Inc. 10700 N De Anza Bird Cupertino, CA 95014 (408) 255-0900 Larry Regle Marketing Manager	j 7µm	. ј Sµm	S <sub>p</sub> .m		./ 7µт	J Species		*	(not defi. ad)	Typical engineering qualification run: 85,000	Working plates, PG or data- base tape	
General Instrument Microelectronics Division 600 W. John St., C.S. 620 Hicksville, NY 11802 (516) 733-3611  J.E. Edwards		dens (Syum)				/ 5pm (10pm)	-	•	50 waters	Prototype run (including mask costs): \$8000 (50 tested protritypes or \$ wafers out)	Cama GDSII tape (preferred). PG tape. masks	
GTE Microcircuits 2000 W. 14th Street Tempe, AZ 85281 (602) 968-4431 Fred M. McWittams Sales Managur, Salcon Foundry		J Span		,		4µm, ISO <sup>2</sup> CMOS, 4µm	J Linear	٣	100 welers/yr. (engineering qual. runs: 25 welers)	Consult fectory	Calma tape, masks, PG tape	
Flarris Semiconductor P:O. Box 863 Melbourne, Ft. 32901 (305) 729-5681 Dennis Gaetano Mgr., Mkg. Planning	/ Sµm (15µm)		J Spm (1Spm)	/ 4µm (10µm)		/ Зµт (Вµт)	/ STL, 2-layer metal, 14µm metal pitch	4° MOS; 3° b- poler	\$100,000 ye.	Consult factory	PG tape or Calma tape (preferred); masks	
Hughes Aircraft Co. Solid State Products Div 500 Supenor Avenue Newport Beach, CA 92663 (714) 759-2964 P. Jennifer Huffer Div. Advart. Manager					j djem	/ 3µm		3" and 4"	25-water bits	Consult fectory	Calma tape, PG tape	
Intel Corp. 5000 W. Wiltams Field Road Chandler, AZ 85224 (602) 961-8051 Bob Koehler	·	/ HMOSI 3.5µm*, HMOSII 2µm*				/ 2µm° CHMO6		4" and 6"	10,000 unts-yr. ("classical foundry")	Consult factory	Applicon tape, Calma tape	
Marketing Manager  International Microelectronic Products 2830 N First Street San Jose, CA 95134 (408) 262-9100  Bob Gerdner Marketing Manager		/ 3µm (8µm), 4µm, 5µm				/ Зыт (Выт), 4ыт, 8ыт	•	ď	\$50,000 yr.	Prod cost (Sµm CMOS): \$6500 to \$6500 plus mask costs	Celma tape or Applicon tape (preferred), masks	
Marketing Manager  Micrel 1235 Midas Way Surnyvale, CA 94086 (408) 245-2500  Stan Ericason Director, Sales-18ktg		/ 4µт (10µт)	/ 4µm (10 <sub>µ</sub> m)	/ 4µm (10µm)	,* 4µm (10µm)	/ 4µm (10µm)	/ Linear TTL	r	25 water starts	Engineering run, (25 water starts): \$2500	Database tape, masks, PG tape	
Micro-Circuit Engineering, Inc. 1111 Farfield (Inve W Palm Bouch, FL 33407 (306) 845-2837 Drk Schwebe Marketing Manager					ј Бјит (10 <sub>ји</sub> т)	/ Տատ (10ատ)	bifet and biMOS processes; 20V, 40V, 80V	e e	Order sommoment, \$100,000	(consult factory)	Celme tape, Cif, masks, PG tape	

<sup>, &</sup>quot;Intel M645 "effective channel length" which may be a lower number than the aquivalent "drain channel length" apecified by other vendors

		•							
Processed									
(water protong, packaging, terting, etc.)	Normal Sumeround Time	Weler Acceptable Criteria (sid process control monitor)	Technical Interaction Between Foundry and Customer	Availability of Design Rules for Vanous Processes	Must Custome: Sign Non- disclosure Agreements	Simulator Parameters Avertable	Second- Source Agreements	Wa Foundry Modity Process?	Processes Available Within Next & Munitis
Probing: packaging: packaged- pari testing burn-tr	Masks to waters: 4 whs (typical) Add 1 wh for 6.35embly/test of amed tots	Four-Phase or customer- supplied PCM Wit also work on a good de-permater backs	"Constant" Interaction	All	No .	Available (not specified) but "serely requested"	(no formal egreenients)	Yes	Some 4"water production by 4083 Plans to increase volume in 4 µm Sigate CMOS process by 3083
Probing, packaging, packaged- part testing	Calma tape to waters: 8-10 weeks (typical) Add 2-3 weeks for packaged devices	Electrical parameters measured on GI 'est eleuctures	Initial review, tohow-up reviews as required	All (3 <sub>µm</sub> process specs not finel as of 4/25/83)	Yes .	(not available)	(no formal agreements)	Yes (within firmts)	3µm Signate nMOS process avait 4083 3µm Signate CMOS process avait 4083
Probing, packaging	Masks to waters: 5-6 weeks (typical)	GTE-supplied PCM	Periodic process and design reviews	AB	Ves	SPICE. TEGAS	Made	Maybe (depends on size of order)	3 <sub>m</sub> m, 2-layer metal 5-pate CMGS avail. SQ83
Probing, packaging, packaged- part lesting, burn-in	Calma tape to probed waters: 10-12 weeks (typical) Add 6-12 weeks for packaged, tested parts	(negotable)	Depends on customer requirements	Al	Yes .	SLICE (Harris' version of SPICE)	(Rone)	Ves of it makes "business sense")	2µm, 2-layer metal CMOS, under develop- ment for gate arrays, should be avail, as foundly process by end of 1983
Probing packaging, packaged- part testing	PG tupe to mests: ,10 days Mastis to finished waters: 25 days	Standard Huges PCM	Pariodic process and design reviews	43	Ves	SPICE (worst-case process modules)	Yes (not apacified)	Vas (il volume warrants il)	(nat specified)
Protting, packaged, parkaged- part sisting, character- ization (skew runs)	Database tape to tested waters (prototype run): 9-12 weeks	Intel PCM ahrays stepped into water	Intel prefers to work with outstomers who design chips chips using the ICEL <sup>4</sup> standard cell program	All	Ves	ASPEC (usually reqs. non-disclosure agreement)	No	No	(not specified)
Probing, packaging, packaged- part testing, burn-in	Database tape to packaged lested parts: 6 weeks (5µm) 7 weeks (3µm CMOS) (3 weeks cycle avail at added cost)	BMP PCM (preferred) or customer- supplied PCM	Inital review plus any necessary tollow-up	Al	Yes	Available (not specified)	Comdial (others in negotiation)	Yes (usually for eng prototype sun only)	2-layer poly and 15V CMOS processes by 4063 2-layer metal by 4083
Probing, packaging, packagod- pert tosting, burn-er	PG tape to waters 5-7 weeks (typical) Add 3-4 weeks for peckaged, tosted devices	Morel- or customer- supplies PCM	Initial review, tohowup reviews as required	All (design rules generally supplied by oustomer)	No (Micrel will sign non-drict for cust supplied nives)	(not available)	Will modify process to be mask compatible with prime source	Yos (see left)	4" waters by 4083 Schonky TTL (3-u ep.) by 4083
Probing, packaging, packaged- part testing	Calms tipe to —- packaged tested samplus: 7-11 weeks	MCE-supplied PCM	Penadic processidesign neviews	AI .	Ves	SPICE. ASPEC-G2	Yes Linear Technology Corp.	Ves	3µm oxide solate J Si-gate CMOS by 12 83 20V detective split types by 12 R3 40V detective stol bipular by 12 83

				mum Featu	pes Aveleti re Size Get h ehown en		.)		Minimum Production	Cost Par	Design Format from Customer	
Company Contact Parson	M+G	MOS S-G	Mo-G	Mos 6-G	Me-G	MO. S-G	Byoter	Prod. Water Size	Paquirements (5 or waters per year)	Prototype Run (with prod cost, if everlable)		
Mitel Semiconductor 360 Legyet Drive P.O. Box 13320 Kanata, Ortano KZK 1XS Canada (613) 532-5630 Gene Cohen Custom Prod. Line Mgr.					,	~ 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5		4	Water run: 20 waters Order: \$10,000	(sec left)	Canta laps, PG laps, masks	
Mosfet-Micro Labs, Inc. Pern Centre Plaza Ouekartown, PA 18951 (215) 536-2104 Robert O. Campbell Marketing Manager	Эмля	/ 3µ/h (also tung- sten gete)	/ Syrn	J Sym	ý Spm	/ 3µm (siso amp- son gate)	-	3"	Prod. cost: \$2000 (me- gate pMOS, nMOS) to \$3500 (Si- gate CMOS)	(nee left)	PG Inpe, masks	
National Semiconductor 2900 Semiconductor Drive Sarta Clara, CA 95051 (400) 737-6055 Richard Y. Barck Dir. MOSALSI Midg.	J Sum	/ Sure, dum to Sure	g Bysta		/ Туыт	Julia Single and dual poly, Syun dual metal	PL, SV Schottky; 5-100V non- Schottky; SV gatd-daps	€ and 5°	Business per family: \$159,000 to \$200,000 yr. (Not inter- asted in prototype business only)	Prototype lot charge (not incl masi/lest charges): \$225-water (me-gate) \$350-water (Si-gate)	Celms tape (preferred): Applican tape, masks, PG tape	
NCR Corporation Microelectronics Div. 2001 Denfield Court Ft. Colons, CO 80525 (303) 226-9580 Dave Nowman Prod. Strategy Mgr.		J Syste Simple or dust motal				/ 3µ/n (7.5µ/n) single or dual metal			500 wafers for non-sid. processing; 100 wafers otherwise	(consult factory)	Calma tape (preferred); PG tape, masks	
Nitron 10420 Bubb Road Cuperino, CA 95014 (408) 255-7550 Robert Miller VP, Mildg. and Sales					/ Տրտ (12µm)	/ 4μπ (12μπ)		3" and 4"	\$100,000 yr. (including sign-recur- sing costs)	(consult factory)	Calma tape, PG tape, masks, rendes	
Plessey 1641 Kacor Avenue Irvine, CA 92714 (714) 540-9937 Peter Minett Product Midg Mgr		/ 5µm (10µm), 6µm (12µm)				/ 2.5 <sub>7</sub> ,m (Вµт), 4µт (9 6µm), 5µт (12µm)	J 3µm ECL, 4µm ECL	3" and , 4"	\$50,000 yr. ·	(consult factory)	Calma tape, mesks, PG tape	
Polycore Electronics, Inc. 1107 Tournahne Drive Newbury Part. CA 91320 (805) 498-8832 S.K. Leong Vice President					/ 7µm (>20V process evail)		/ Linear, Pi- defectno isolation combination CMOS: Brear	r	24 water engineering lot	Engineering - nurs: \$3020 to \$6000 Production costs (avg.): \$100 water (CMOS) \$130 water (finear)	Worlung plates	
RCA Solid State Drv. Rt. 202 Somerville, NJ 08875 (201) 665-6000 Jurgen W. Schwer Mintg. Myr., Custom Products					ј 7 <sub>р</sub> л	/ Зµт, - Бµт СМОБ/ ВОВ. Зµт, 4µт,		4" CJ' SUMOS/ SOS)	(consult factory) (RICA offers toundry services on selected basis only)	Evaluation- tot costs \$20,000-\$30,099 Tooling costs \$10,000-\$20,000	Celma tape	
Semi Processes, Inc. 1971 N. Capital Ave. Sen Ave., CA 95/132 (408) 945-1500 C.B. Detrick Waler Service Mgr.					4.Spm	J 4.Sµm		r	(not apacified)	Typical cost for evaluation num (CMOS megate): \$2500	Masks	

Pos' Wa'er									
Pricessing Services (we'er pricing puckeying, escript etc.)	Normal - Turnaround Time	Water Acceptable Critena (std process control monitor)	Technical Interaction Between Foundry and Customer	Availability of Design Rules for Vanous Processes	Must Customer Sign Non- disclosure Agreements	Simulator Parameters Available	Second- Source Agreements	Wile Foundry Mosky Process?	Processes Available Witten Next 6 Monets
Probing. packaging packaged- part secting	trasks to waters: 6 weeks (typical) Add 4 weeks from PG tape, add 2 weeks to packaged parts	Metal PCM	Technical general meetings gossible	AZ .	Ves	SPICE	GTE Microonulis	Yes (negotable)	(not specified)
(services evaliable locally elsewhere)	Masks to test prouts 3 to 4 weeks	(Nexòle)	Interaction with MML's engineers/ technicians as required	Selfs layout rules for \$250	_	(not available)	(sometimes)	Yes	High-votage MOS, also working wifi V-groove LIOS
Probing. packaging. packaged- part testing. reliability processing	Database tape to PCM-tosted waters: 6 to 10 weeks (depending on process) For packaged parts, add 4 to 6 weeks	Standard National PCM	Instal and follow-up process/design reviews as required	AS	Ves	SNAP (NSC internal)	Yes (not specified)	Yes (mnor)	2µm double- metal n-well CMOS; mid 84
Probing. packaging, packaged- part assing, burn-in	Calma tope to tested waters: 6 weeks (typical)	Prefers to step-in NCR PCM	evital review Followup structure as necessary	Negotable		SPICE	Not yet (in negotation with 3 large companies)	Yes (depends on volume)	Will be able to manufacture devices (with poly-to-substrate capactors) for analog functions in CMOS circuits by end of 1953
Probing, packaging, packaged- part tosting, butti-in	Masks to tested waters 4 to 6 weeks From PC tape add 2 weeks, to peckaged lested parts; add 4 weeks	Nitron PCM (preferred) or customen supplied PCM	Initial and follow-up process/design reviews	For older processes	Yas	(not available)	Universal Semiconductor (Si-gate)	Yes (within hmits)	3µm S-gate CMOS available by 1084
Probing, packaging, packaged- part testing	Masks to waters: 2 wks PG tape to tested devices: 6 wks	Plessey PCM	Inital review	A	Yes	SPICE	Yes (not specified)	No	2.5-µm CMOS by end of 1983
Probing, (packaging in far East and testing can be arranged)	Fast-turnaround engineering runs, masks to waters 2 wis (CMOS) 3 wits (knear) Add 2 to 3 days for sample packaging	Polycore- supplied PCM	Intial review	AI	No	(not available)	(no formal - agreements)	(es	(not disclosed)
Probing, packaging, packagod- pari testrig, burn-in	(not specified)	RCAs Water Acceptance Test (WAT) onlenge	Instal formal design reviews (required)	AJ	· Yes	R-CAP	(no formal agreements)	No	(none)
Basic testing	Masks to waters: 4 wks. (me gate CMOS) 6 to 8 wks. (Si-gate CMOS)	Mulually agreed-upon PCM	Penodic interestion	AI .	For Si- gate CMOS process enly		(not specified)	Yes	5" water production by end of 1983

				num Feet.	pes Avaitable se Size Gere habown in j		.)	-	Minimum Production	Cost Per		
Company Corkect Person	MeG	MOS 6-G	Me-G	vos s-g	M+G C	MUS 8-G	Bipoler	Prod Water Size	Requirements (\$ or waters per year)	Prototype Run (with prodicost, if available)	Design Format from Customer	
Silicon Systems, Inc. 14351 Mytord Road Turon, CA 92650 (714) 731-7110					/ 7µm (12µm)	(ghu) 3hu 1	J Ameton- inotated (12V V <sub>CE D</sub> ), 14µm	4"	\$20,000/yr.	(consult factory)	Calms tape, CIF, masks, PG tape	
Bob Schultz Director, Gustomer Servs					[ [							
Solid State Scientific, Inc. 3000 Webs Road Water Grove, PA 19090 (215) 657-6400 John J. Wunner Director of Mag.		/ Zpm			./ 6µm	J 3μm ·		4"	\$250,000 over first year	\$15,000 to \$30,000 to produce packaged prototypes from PG tape	Applicon tape, PG tape	
\$1C M.crotechnology 2270 S. 85th St., MD G1 Lnusyne, CO 50027 (303) 673-4307 Lon Hieff		j 3µm (1- or 2- inyer metal)		J 3µm (1- or 2- layer metal)		/ 3µm (1- or 2- layer metal)		<b>4</b> *	500 waters or 82 <sup>4</sup> 0,000ys	\$10,000 for first 20 waters	Calma tape, Applicon tape, CIF, PG tape, masks	
Supertex, Inc. 1225 Bordeaux Unive Summyrale, CA 94096 (408) 744-0100 Richard Segel					/ 5µ/п (10 <sub>µ</sub> /п)	/ 5µm (10µm)		4"	Lot 24 waters	Engineering lots: \$4800 to \$8400	Masks	
Vice Provident Sales  Symertek (a subsidiary of Honeywell) 3001 Stender Way Santa Clara, CA 95054 (408) 748-7045  Dan Carlson COT Marketing		/ 2μm (6.5μm), 3μm (9μm), 5μm (10 and 11.5μm) single & double poly			·	J 2μm double poly (6.5μm), 3μm (9μm) single & double poly		£	5 water nuns per year (20 waters out per nun)	Production cost: \$250 to \$400 per water	Caima GDSII (prefered), PG tape, masks	
United Microelectronics Corp. 305/A Scott Boulevard 5 anta Clara CA 95050 (408) 727-9239 Troy Speers Marketing Manager		/ 3µm (7µm)			/ 5µm (10µm)	/ 3µm (8µm)		e <sup>r</sup>	Production nun: 24 wafers (engineering prototype nun: 10 wafers)	Engineering waters \$200 each (minimum 10)	Calma tape, InG tape, masks	
Universal Semiconductor, Inc. 1925 Zanker Road San Jose, CA 95112 (403) 279-2830 Barry Boutton Sales Manager		/ 5µm (10µm				y single and double poly 3μm (10μm), 5μm (10μm)		4"	500 waters (ong-neering nuri 50 water starts)	Engineering run \$15,000 plus tooling (\$25,000 plus tooling without product commitment)	Calina tape, Applicon tape, PG tape, masks	
VLSI Technology, Inc. 1101 McKay Drive San Jose: CA 95131 (400) 942-1810 Tony Valenting Manager,		/ Зµт (7.0µm) HMOSI, Sµm				/ Sum n-well process via Japan source		*	Production lots: 10 waters Prototype runs 5 waters SAAP: product waters (MPW) 20 packaged, uniested devices	MPW run \$5000-\$7500 Typical wate: rharpes (4 .4s: Dipolyh- put) \$400 water (5 um nMOS) to \$700 water (4 um CMOS)	CIF, PG tabe, Calma tabe, (also masks for standard processing)	
7yMOS Corp FO Bar 62379 Surriyalir CA 94088 (408) 730 8800 -Cirll Veughn COT Metg. Manager					/ ՏբՊ (10 <sub>բ</sub> m)	/ 5µm (9µm), 3µm (6µn) en dovel		*	6-water prototype nun plus 50 waters yr (eng. proto- type nun 10 waters)	6-water proto- type nun \$4800 to \$5000 Production voluniar costs \$270 to \$200 per water	Database Inge, PG Inje, Hinsha	

Post Water Processing Services (safer probing packaging lasting etc.)  Probing packaging packaging packaging pathability tekability back-end generating	Normal Tunaround Time Masks to tested waters 6 to 8 wks	Water Acceptable Oritina (8td process control montor) SSI or customer supplied PCM	Technical Interaction Between Foundry and Customer Initial design review	Ave-tability of Design Rules for Vanous Processes	Must Customer Sign hon- disclosure Agreements	Simulator Parametors Available SPICE	Second- Source Agreements (no formal agreements)	Wite Foundry Modify Process? Yes (depends on volume)	Processes Available Within Next 6 Muritis Washed e-trittar Dipolar process available 4083
Probing, packaging, packaged- plant testing, qualification/ screening	PG tape to tested waters: 10 to 12 wis.	Shepped-in fust sites (source not apecified)	Initial process/ design reviews, further assistance as required	AI	Yes	MSINC (SPICE evaleble econ)	nMOS process compatible with Standard Microsystems	Yes (depends on circum- etances)	(none)
Probing, packaging, packagid- part testing, charac- tenzation	Masks to tested waters: 2 wks. From PG tape: add 1 wk. From CIF or CAD database tape: add 2 wks. To tested pkg. parts: add 2 wks.	STC PCM	Various process/ layou/design www.saveleble	A	Yes	SPICE MOS2 model parameters	(available but not specified)	Yes	2µm Si-gate CMOS and nMOS processes, 1 or 2-layer metal by 4083
Custom handling	Masks to fusted waters: 4 to 6 w/ks. (me-gate) 5 to 8 w/ks. (Si-gate)	Superiex- Buppied PCM	Process parameter reviews	At	Yes	(not evailable)	No formal agreements (claims to be mask compat- ble with Mitel, GTE, and AMI)	Yes	4μm S⊷gate CMOS by 4O63
Probing, packaging, packageri- part lesting, burn-in	Celms tape to waters: 10 wks. From PG tape: 8 wks. From masks: 3 to 5 wks.	Syneriek PCM required on at least 3 of 5 lest sites	Depends on a tomer requirements	AI	Required for 2µm and 3µm processes	Provide SPICE simulation (but not actual SPICE model)	Some (not specified)	Yes (mp:ant loveis only)	5"water processing capability by 1Q84
Probing, peckaging, packaged- part testing	Masks to waters: 3 wks From PG tape: add 1.5 wks. To prockaged parts: add 1.5 wks.	PCM (source not specified)	Initial design: nute exchange/ review	AI	Yes	Some SPICE and ASPEC parameters available; not complete for 3µm process	Mask compatible with AMI Si-gate CMOS	Yes	3μm 2-layer metal and 3μm 2-layer poly CMOS process available by 4083
Probing, packaging, packaged- part terbing	Masks to probed waters 5 whs From PG tape add 2 wks; to packaged samples; add 1 wk.	Prefers Universal PCM stopped in, but will accept customer PCM	Infial review, orcuri design and CAD support	AJ	Yes	SPICE2G	Siliconia and Nitron (others in Regoliation)	No ·	2µm oxide- isolated CMOS by Dec. 1983
Prohing, packaging, packaged- peri tirsting	Database merge to packaged parts (MPW), 4 m/s. Masks to waters (standatione product) 2.5 wits.	VTI-supplied PCM	Process com- patibility and prototype ventication reviews	AJ	Ves	SPICE, ASPEC	Ricoh Corp. (Japan)	Yes (V <sub>T</sub> only for low vulume)	2 5µms HMOSII avarable by 3023 3µm in with CMOS in August 1925 3µm bein tub CMOS 4063 24ayer metal CMOS ava lutin by end of 1443
Proting packaging, packaged- part testing high temp and mill std testing	Masks to waters: 3 to 4 wks Fts time to waters 5 to 6 wks And 1 wk for firsted prototypes	ZyMOS-supplied PCM (nearly, proprietary, available to other IC makers)	Initial and fotour on fortows as required	As	No	Most SPICE parameters available	Intel (3-u HCMOS) Lalls outer processes "industry standard"	Slight adjustments only	3 µHCMOS avalithe in 2nd half of Esio3